

WHAT IS CLAIMED IS:

1. A method of cleaning a substrate for removing dirt on the substrate, comprising: irradiating a substrate surface with ultraviolet rays including wavelengths of 184.9 nm and 253.7 nm in an oxygen-containing atmosphere, and then subjecting the substrate to wet cleaning with pure water.  
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2. A method according to claim 1, wherein said oxygen-containing atmosphere comprises atmospheric air.  
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3. A method according to Claim 1, wherein said ultraviolet rays are generated from a discharge lamp.  
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4. A method according to Claim 1, wherein said ultraviolet rays are generated from an excimer laser.
5. A method according to Claim 1, wherein said ultraviolet rays are generated from a plurality of sources.  
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6. A method according to Claim 5, wherein at least one of the sources issues a wavelength selected from 184.9 nm and 253.7 nm.  
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7. A method according to Claim 1, wherein at

least one of the wavelengths of 184.9 nm and 253.7 nm is a peak wavelength.

8. A method according to Claim 1, wherein the  
5 substrate is irradiated with ultraviolet rays at an  
intensity of at least  $0.2 \text{ J/cm}^2$ .

9. A method according to Claim 1, wherein the  
substrate is subjected to the wet cleaning with pure  
10 water within 30 min. after the irradiation with  
ultraviolet rays.

10. A method according to Claim 1, wherein said  
substrate comprises a glass substrate.

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11. A method according to Claim 1, wherein the  
substrate is subjected to the wet cleaning when the  
substrate surface shows a contact angle with water of  
at most 10 degrees after the irradiation with  
20 ultraviolet rays.

12. A method according to Claim 1, wherein the  
substrate comprises a substrate for a liquid crystal  
device.

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13. A method according to Claim 1, wherein the  
substrate comprises a glass substrate provided with a

transparent electrode.

14. A method according to Claim 13, wherein said transparent electrode comprises indium tin oxide.

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15. A method according to Claim 1, wherein the substrate after the wet cleaning is further irradiated with ultraviolet rays.

10 16. A method according to Claim 15, wherein the ultraviolet rays include wavelengths at 184.9 nm and 253.7 nm.

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